

Abstract

Method for fabricating a trench isolation structure

- 5 A method for fabricating a trench isolation structure,
including forming a mask on a substrate, forming at least
one trench in the substrate with the mask, carrying out
selective deposition of a first insulation material to at
least partially fill the at least one trench in the
10 substrate with the insulation material in the presence of
the mask, and applying a second insulation material over
the entire surface of the structure in order to fill the
at least one trench in the substrate at least up to the
top side of the mask.

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